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WHAT IS CLAIMED IS:

5 1. A flat-panel-display substrate formed by sintering a mould comprising glass powder and a filler made of metal oxide and/or semi-metal oxide; the glass powder including alkaline-earth oxide; 15 to 50% by weight of silicon oxide; and no greater than 2% by weight of boron oxide; the filler being at a concentration of 10 to 30% by volume of the total amount of the glass powder and the filler in the mould; 10 the mould's average coefficient of linear thermal expansion being from 7 to 9.5 ppm/°C in a temperature range of 25 to 700 °C; and a sintered body obtained from the mould including crystal phases.

15 2. The flat-panel-display substrate according to claim 1, wherein the glass powder includes 35 to 55% by weight of alkaline-earth oxide.

20 3. The flat-panel-display substrate according to claim 1, wherein the glass powder includes no greater than 1% by weight of alkali-metal oxide and no greater than 1% by weight of phosphorous oxide.

25 4. The flat-panel-display substrate according to claim 1, wherein the glass powder includes, as essential components, 25 to 50% by weight of silicon oxide; 5 to 15% by weight of aluminum oxide; and 5 to 30% by weight of titanium oxide and/or zirconium oxide; and as optional components, no greater than 45%

by weight of barium oxide; no greater than 45% by weight of strontium oxide; no greater than 15% by weight of calcium oxide; and no greater than 15% by weight of magnesium oxide.

5           5. The flat-panel-display substrate according to claim 1, wherein the filler includes at least one of alumina, forsterite, and zirconia.

10           6. The flat-panel-display substrate according to claim 1, which is used for a thin film EL element or a plasma display panel.

15           7. A thin film EL element having a lower electrode layer; an insulator layer; a light emission layer; and an upper electrode layer formed on one side of the flat-panel-display substrate according to claim 1.

          8. The flat-panel-display substrate according to claim 7, wherein the insulator layer includes lead and/or bismuth.